

FIG. 1a

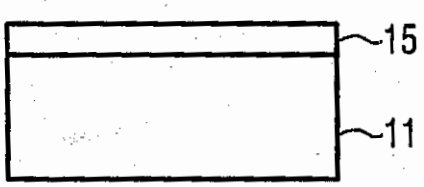


FIG. 1b

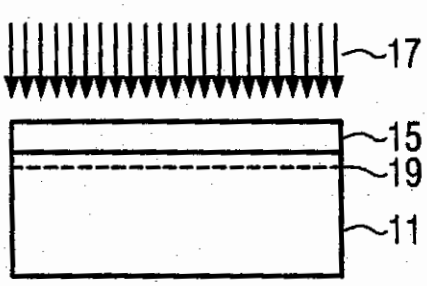


FIG. 1c

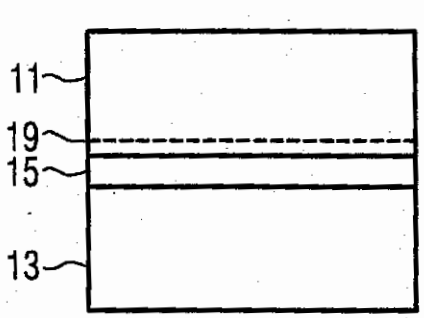


FIG. 1d

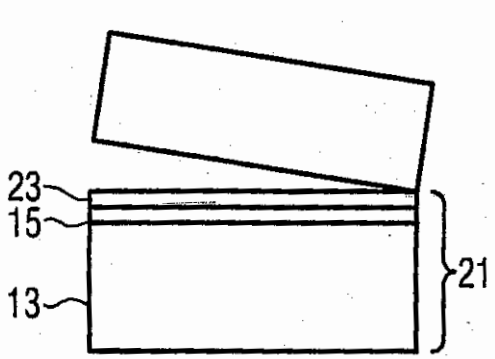


FIG. 1e

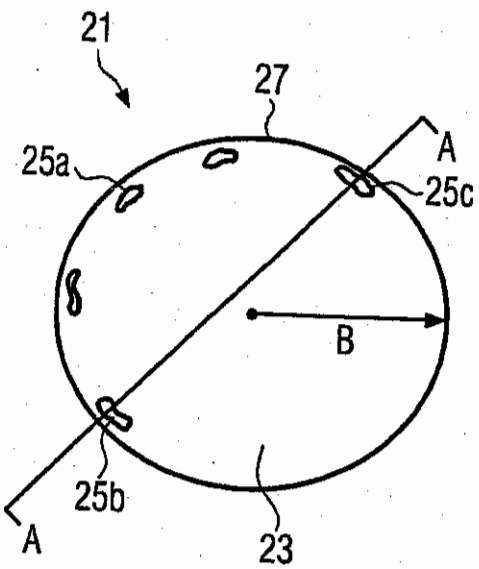


FIG. 2a

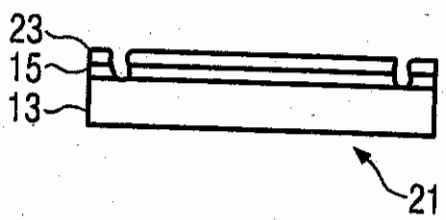


FIG. 2b

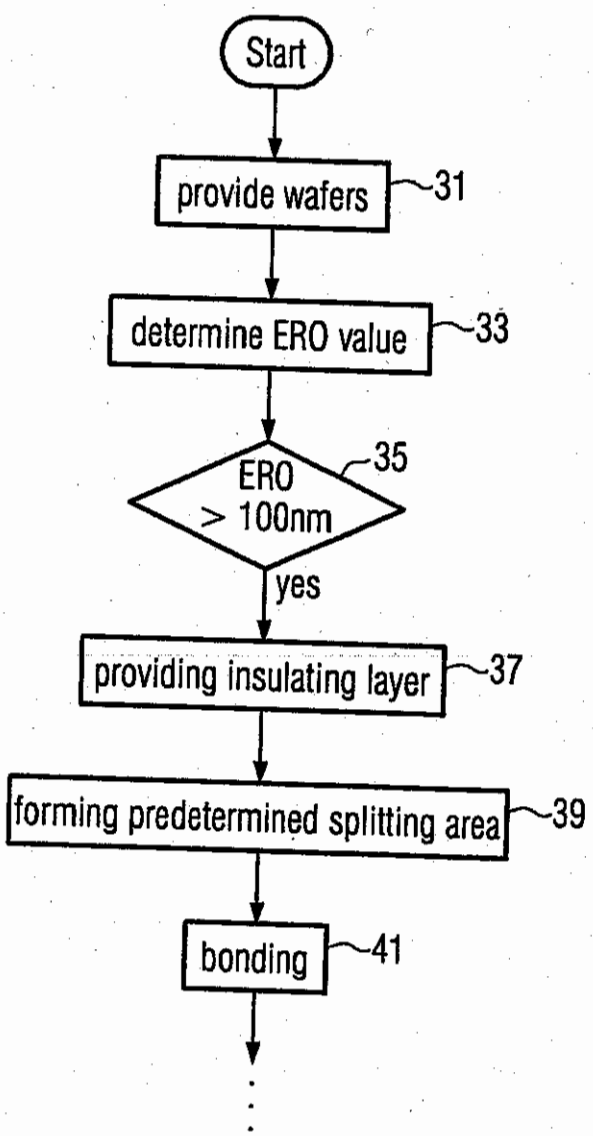

Start
provide wafers
31
determine ERO value
33
ERO
> 100nm
35
yes
providing insulating layer
37
forming predetermined splitting area
39
bonding
41

FIG. 3

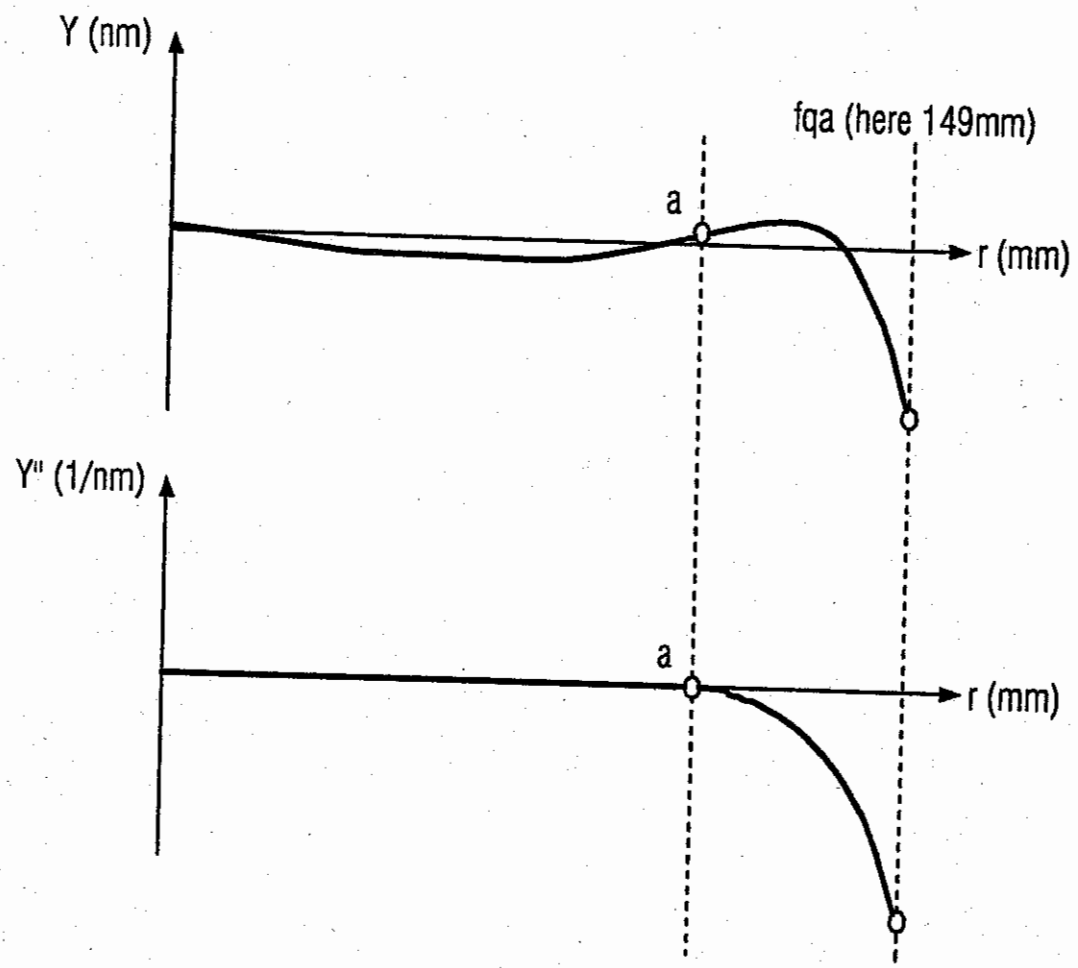


FIG. 4

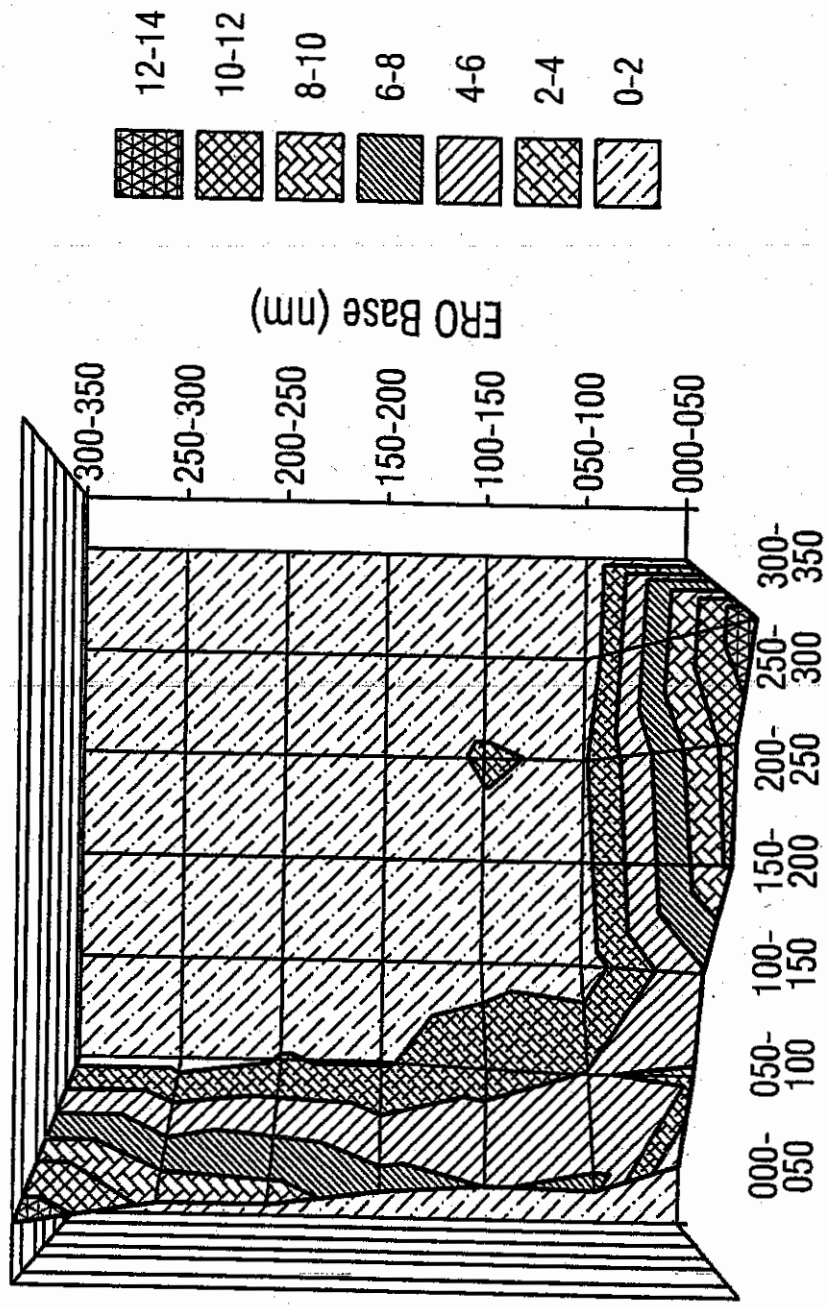

12-14
10-12
8-10
6-8
4-6
2-4
0-2
ERO Base (nm)
300-350
250-300
200-250
150-200
100-150
050-100
000-050
300-350
250-300
200-250
150-200
100-150
050-100
000-050
ERO Top (nm)

FIG. 5